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Patent

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USPN 09/375,267  
Atty Docket 99108

AF/2221

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of:  
HANS LOSCHNER, ET AL.  
For: PARTICLE MULTIBEAM LITHOGRAPHY  
Serial No. 09/375,267 09/375 627 HN  
Filed: August 17, 1999

Group Art Unit:  
2881  
Examiner:  
Anthony Quash

11/D(E)  
FJONES  
2-27-02

EXPEDITED PROCEDURE

AMENDMENT C UNDER RULE 116 AFTER FINAL REJECTION

TO:  
Assistant Commissioner of Patents  
Washington, D.C. 20231

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Dear Sir:

In response to the Examiner's Action, made final, mailed August 14, 2001, applicant requests that the subject patent application be amended as follows:

IN THE CLAIMS:

Please amend claim 1 in the manner set forth below. A clean copy of claim 1 is enclosed herewith.

1. (Twice amended) An apparatus for multibeam lithography by means of electrically charged particles, comprising an illumination system having a particle source, the illumination system producing an illuminating beam of said electrically charged particles, and a multibeam optical system positioned after the illumination system as seen in the direction of the beam, said multibeam optical system comprising at least one aperture plate having an array of a plurality of apertures to form a plurality of sub-beams, wherein the multibeam optical system focuses the sub-beams onto the surface of a substrate for simultaneously writing a plurality of different

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CERTIFICATE OF MAILING

I hereby certify that this correspondence is being deposited with the United States Postal Service on first-class mail in an envelope addressed for Assistant Commissioner of Patents and Trademarks, Washington, DC 20231 on:

Date 11/9/01 2. J. V. [signature]